

ABSTRACT OF THE DISCLOSURE

The present disclosure relates to a replaced photomask including a substrate and a plurality of etched patterns. The plurality of etched patterns are formed on the substrate according to a photomask layout which has a plurality of photomask layout patterns categorized into a plurality of first groups. Each of the first groups includes a plurality of identical initial layout patterns, and each of the first groups is reproduced from an initial layout having a plurality of initial layout patterns categorized into a plurality of second groups to which the plurality of first groups respectively correspond, wherein the plurality of photomask layout patterns respectively correspond to the plurality of initial layout patterns and at least one of the plurality of the photomask layout patterns is replaced by a standardized photomask layout pattern.